



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Robert P. Meagley et al.  
Serial No.: 10/688,521  
Filed: October 17, 2003  
For: Reducing Photoresist Line  
Edge Roughness Using  
Chemically-Assisted Reflow

§ Group Art Unit: 1752  
§  
§ Examiner: Amanda C. Walke  
§  
§ Atty. Dkt. No.: ITL.1026US  
§ (P16713)  
§  
§ Assignee: Intel Corporation  
§

Mail Stop: Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

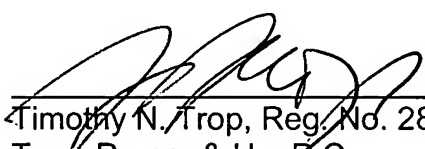
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicant submits the references listed on the attached form PTO 1449, copies of which are enclosed. A copy of a communication dated November 2, 2005 from a foreign patent office in a counterpart application is also enclosed. I, the undersigned, hereby certify that each item of information contained in the Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the Information Disclosure Statement. Please apply any charges or credits to Deposit Account No. 20-1504 (ITL.1026US).

Respectfully submitted,

November 17, 2005  
Date

  
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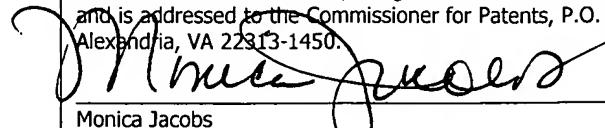
Attorneys for Intel Corporation

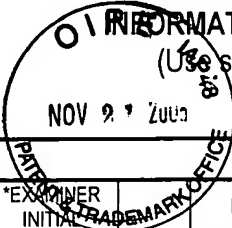
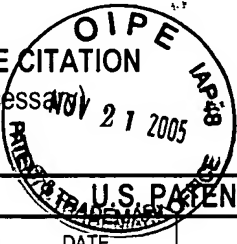
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Date of Deposit: November 17, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

  
Monica Jacobs

<div style="display: flex; justify-content: space-around; align-items: center;"> <div style="text-align: center;">  </div> <div style="text-align: center;">  </div> </div>				ATTY DOCKET NO. 1TL1026US (P16713)		SERIAL NO. 10/688,521		
				APPLICANT(S): Robert P. Meagley et al.				FILING DATE: October 17, 2005
<b>U.S. PATENT DOCUMENTS</b>								
*	EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	A.	6,162,592	12/19/2000	Taylor et al.				
	B.							
	C.							
	D.							
	E.							
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>								
	F.							
	G.							
	H.							
	I.							
	J.							
<b>FOREIGN PATENT DOCUMENTS</b>								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	
	K.							
	L.							
	M.							
	N.							
	O.							
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
	P.	Lin et al., <i>Line Edge Roughness in Positive-Tone Chemically Amplified Resists: Effect of Additives and Processing Conditions</i> , Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 4345, No. 1, Feb. 2001, pgs. 78-86.						
	Q.							
	R.							
	S.							
	T.							
	U.							
EXAMINER				DATE CONSIDERED				

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.